



# **Percolation Threshold Effects on the Electrical Contact Resistance and Adhesion of Microelectromechanical Systems Thin-Film Materials**

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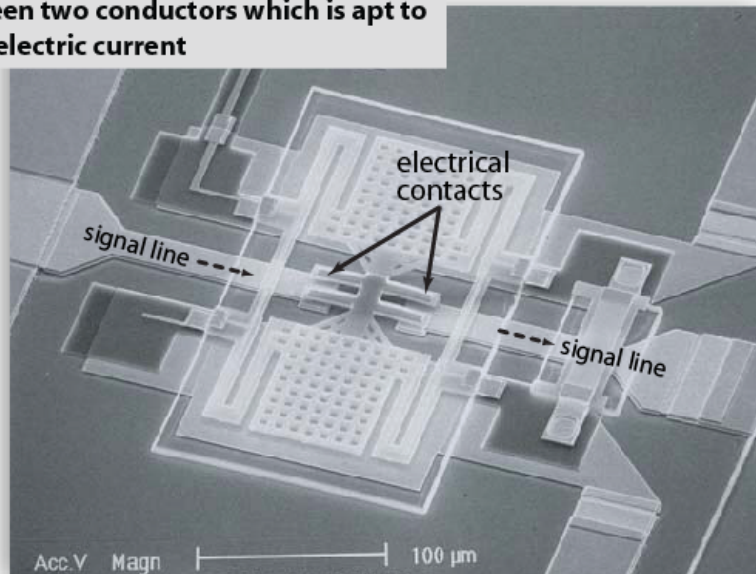


# ***Presentation Outline***

- **MEMS Electrical Contacts**
- **Degradation Mechanisms**
- **Composite Electrical Contact Materials**
- **Experimental Results**
- **Percolation Threshold**

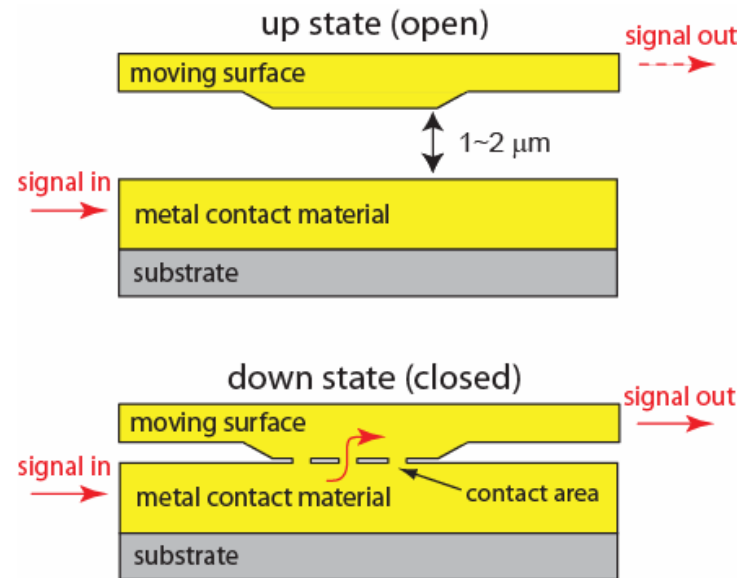
# MEMS Electrical Contacts

**electrical contact** : a reasonable junction between two conductors which is apt to carry electric current



Rockwell RSC MEMS switch

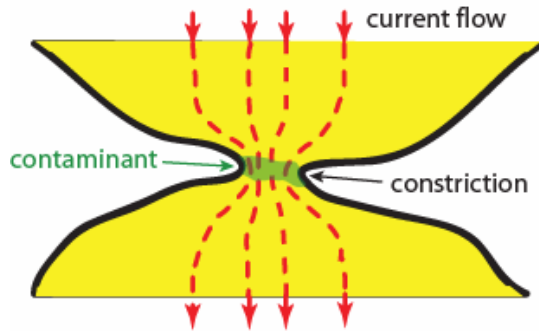
**Metal-contact MEMS electrical devices** are capable of operating over a wide range of signal frequencies and possess distinct advantages over larger solid-state components: (e.g., size, low insertion loss, high isolation, low power consumption)



However, the performance and reliability of metal-contact MEMS devices depends critically on the *quality* of the electrical contact interfaces which can change over time

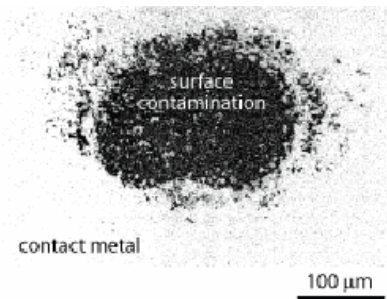
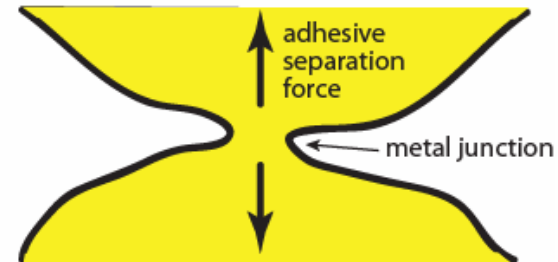
# Degradation Mechanisms

## Reduced Conductivity

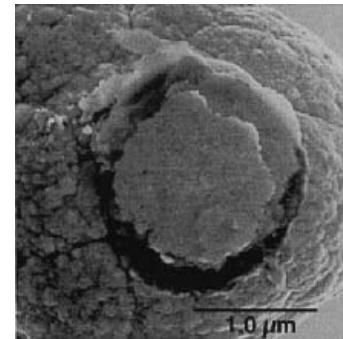


exclusive modes

## Excess Adhesion



Tamal, T., 1995, "Effect of Silicone Vapour and Humidity on Contact Reliability of Micro Relay Contacts," IEEE Transactions on Components, Packaging, and Manufacturing Technology – Part A, 19(3), pp. 329-338.

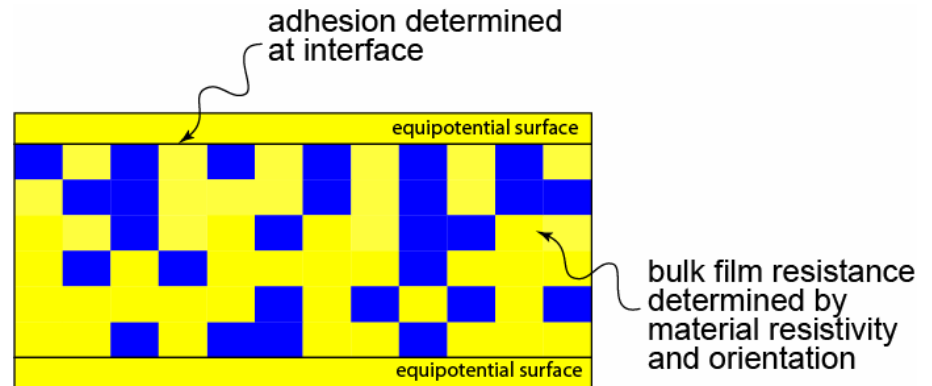
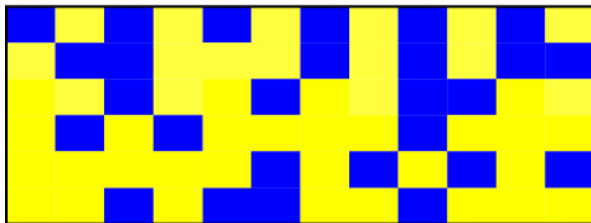
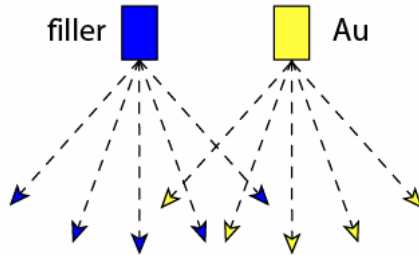


Hyman, D., and Mehregany, M., 1999, "Contact Physics of Gold Microcontacts for MEMS Switches," IEEE Transactions on Components and Packaging Technology, 22(3), pp. 357-364.

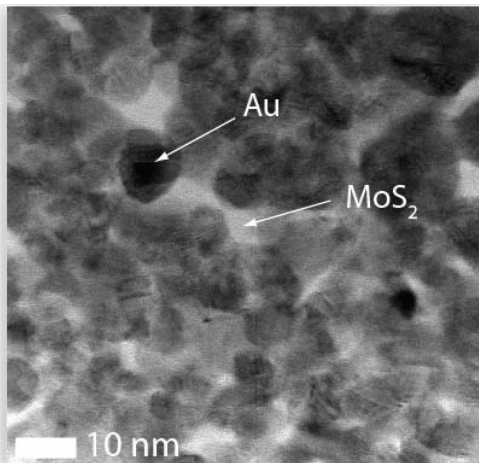
**Proper operation of MEMS electrical contacts is predicated on the balance of sufficient interfacial conductivity and off-state separability of the surfaces**

# Composite Electrical Contact Materials

thin-film deposition



composite thin-film electrical contact

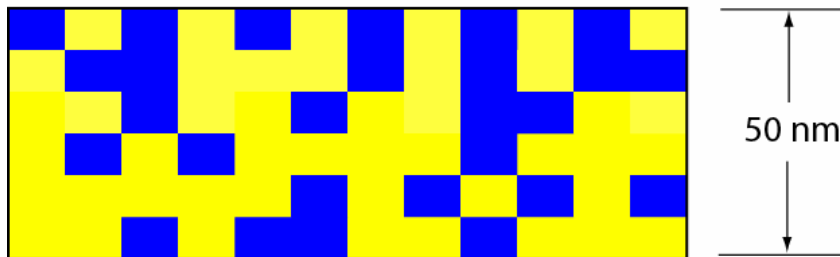
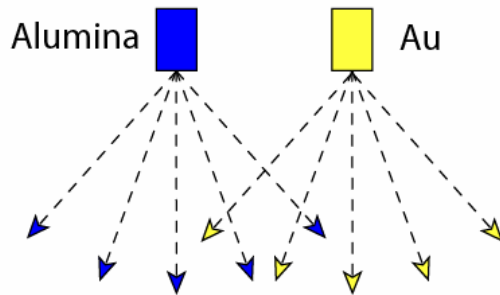


- J.R. Lince, "Tribology of co-sputtered nanocomposite Au/MoS<sub>2</sub> solid lubricant films over a wide contact stress range", *Tribology Letters*, Vol. 17, No. 3, 2004

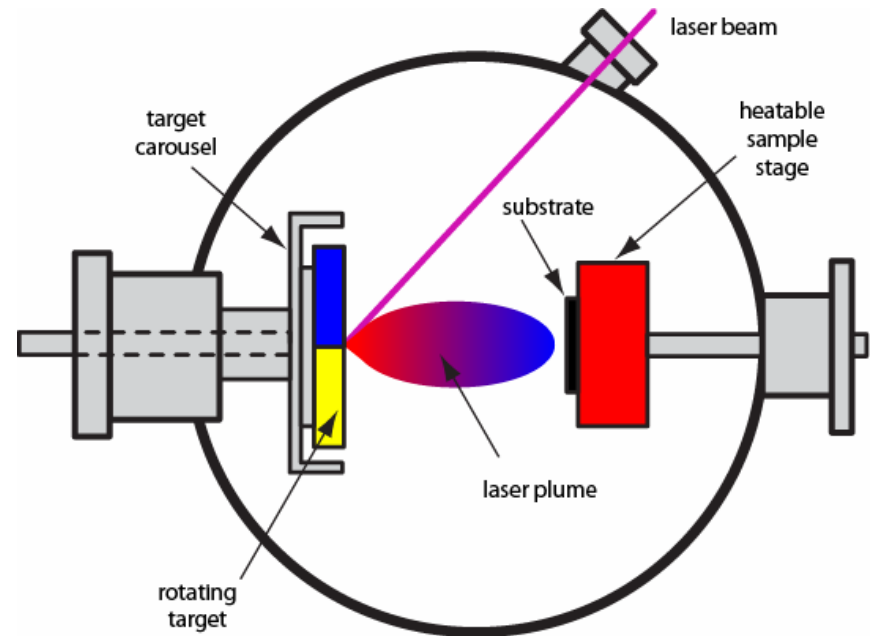
**A co-deposited electrical contact material with intermixed phases of high-conductivity and low-adhesion constituents should satisfy the concurrent operational requirements of low resistance and reduced adhesion**

# Composite Material Deposition

## Pulsed-Laser Deposition

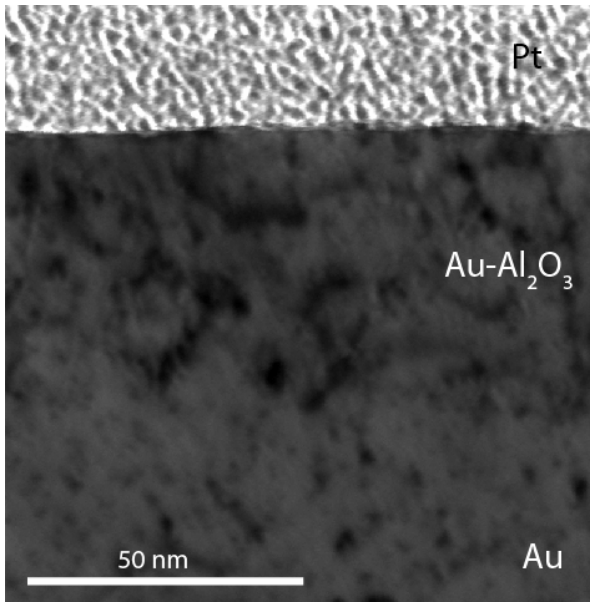


Composite Contact Material

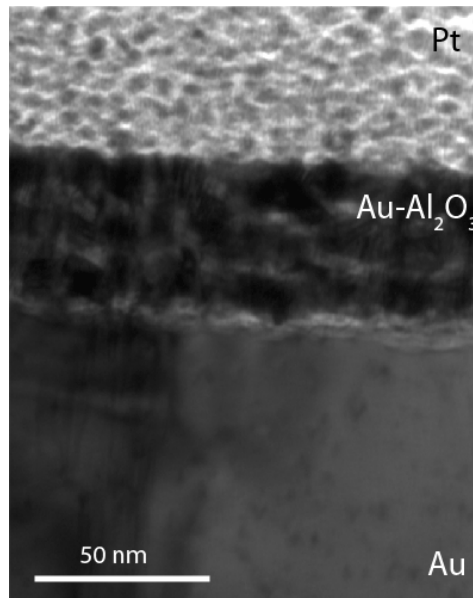


Pulsed-laser deposition (PLD) was used to create thin Au-Al<sub>2</sub>O<sub>3</sub> electrical contact film composites of varied composition

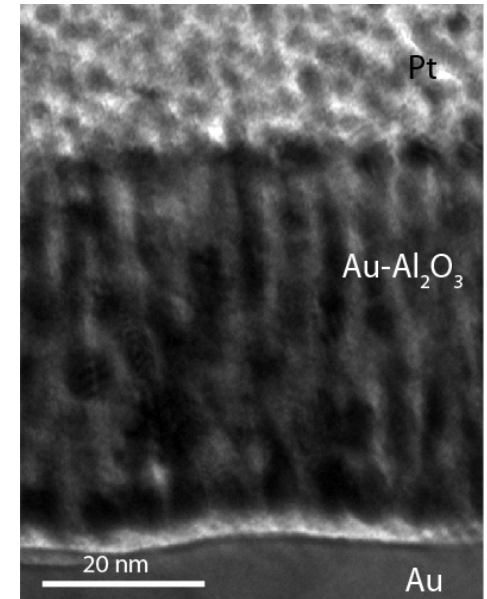
# $Au-Al_2O_3$ TEM Imagery



90% Au



50% Au



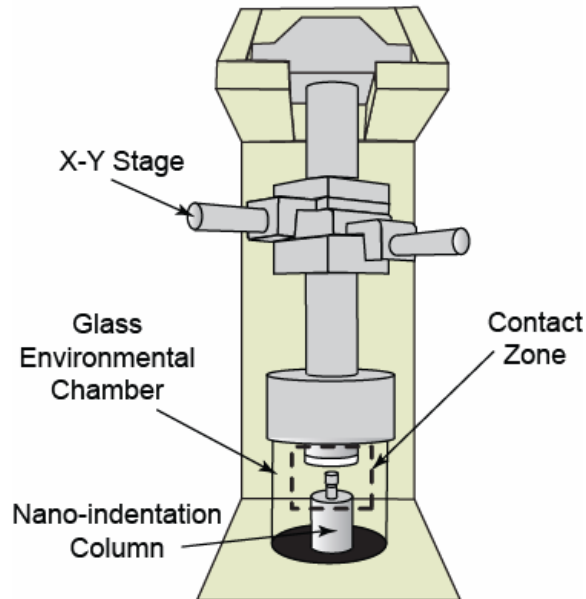
20% Au

**Transmission Electron Microscopy (TEM) imagery of the gold-alumina composites shows evolving morphology within the composite film as gold content decreases**

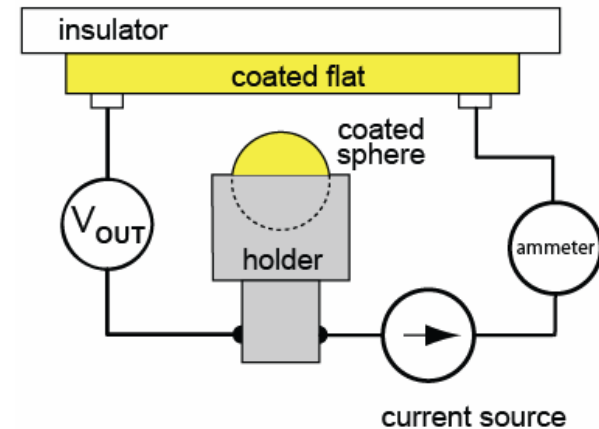


# Experimental Apparatus

## Apparatus Schematic



## Contact Zone Schematic

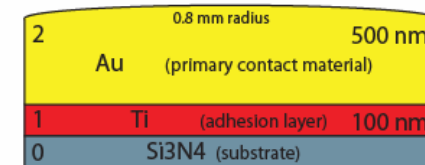
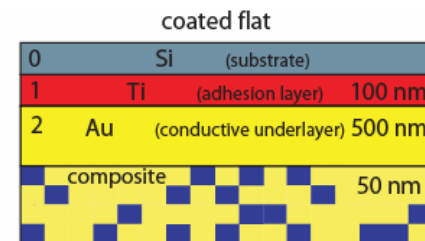
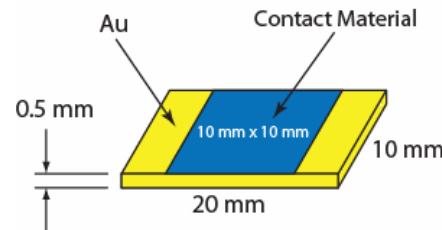


## Conditions

$$F_n = 100 \mu\text{N} (\pm 1 \mu\text{N})$$

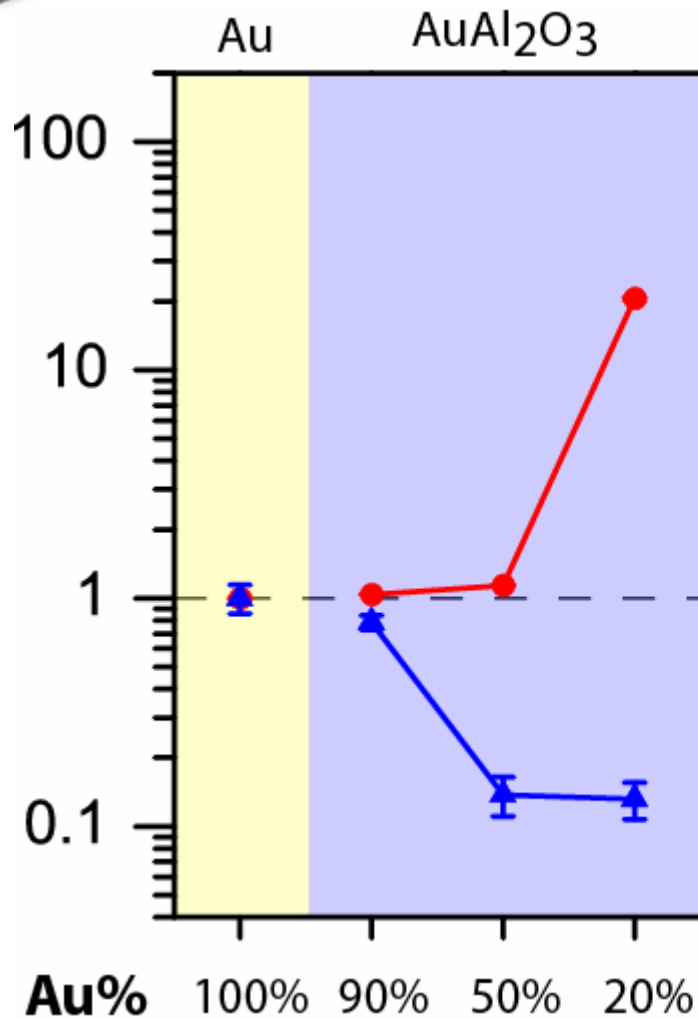
$$V_{open} = 1 \text{ V} (\pm 1 \mu\text{V} @ 1 \text{ V})$$

$$I_{source} = 1 \text{ mA} (\pm 1 \text{ nA} @ 1 \text{ mA})$$





# Experimental Results



● Normalized Resistance

▲ Normalized Pull-off Force

## Normalization Values

$$R_{\text{AuAu}} = 533 \pm 7 \text{ m}\Omega$$

$$F_{\text{poAuAu}} = 253 \pm 36 \text{ mN}$$

## Experimental Conditions

$F_n$ : 100  $\mu\text{N}$

current: 1 mA

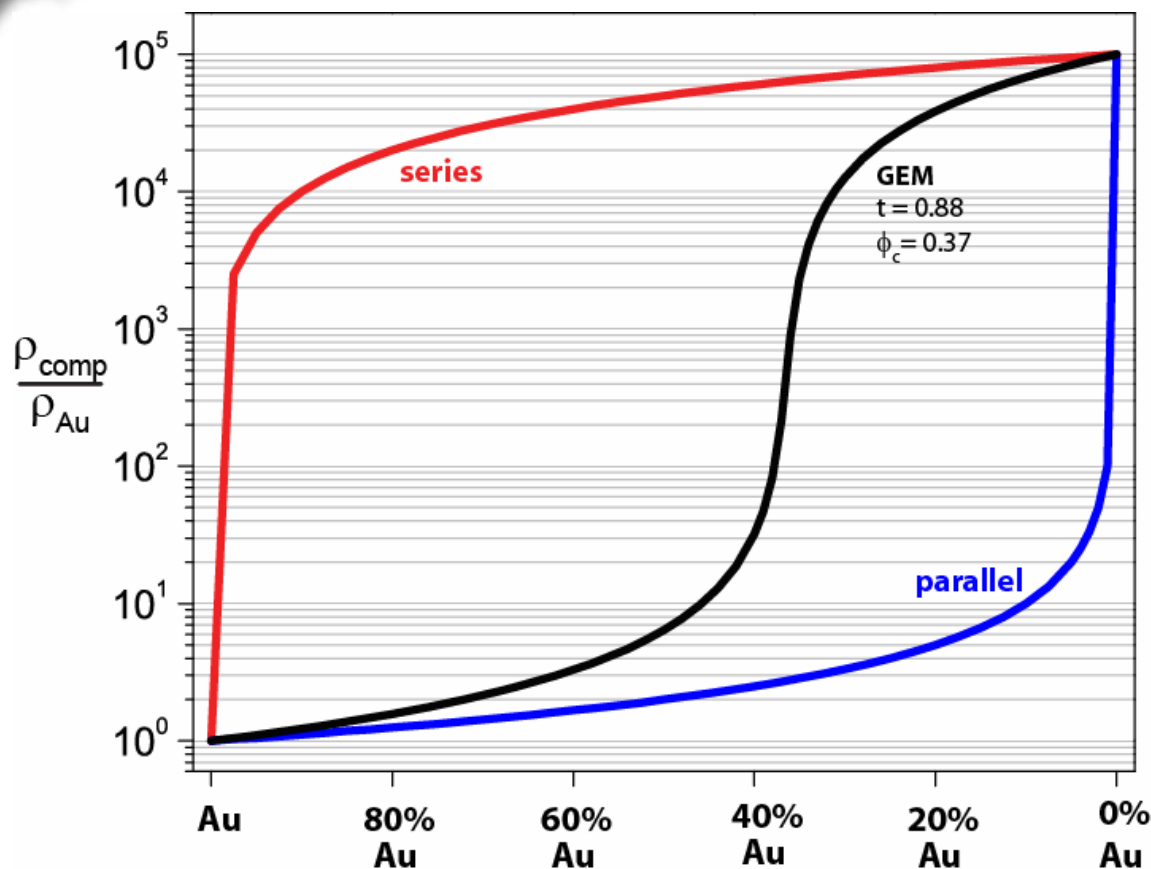
laboratory air

22 °C

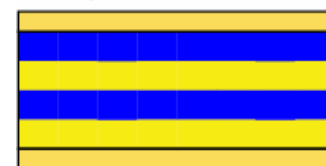
RH 20%  $\pm$  5%

Initial experimental results showed that reduction in adhesive pull-off force did not immediately coincide with increases in measured contact resistance

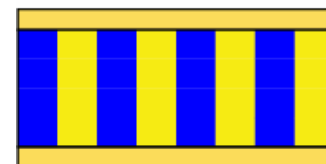
# Percolation Threshold



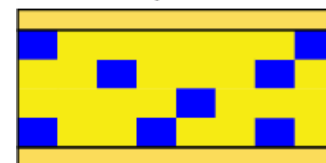
Series (Linear Rule of Mixture)



Parallel Structure



Randomly Distributed



**General Effective Media**  
(McLachlan 1987)

$$\frac{(1-\phi)\left(\rho_m^{1/t} - \rho_h^{1/t}\right)}{\rho_m^{1/t} + \rho_h^{1/t} \left(\frac{1-\phi_c}{\phi_c}\right)} + \frac{\phi\left(\rho_m^{1/t} - \rho_l^{1/t}\right)}{\rho_m^{1/t} + \rho_l^{1/t} \left(\frac{1-\phi_c}{\phi_c}\right)} = 0$$

unknown parameters

$\rho_m$  -- composite resistivity

known parameters

$\rho_l$  -- low resistivity phase

$\rho_h$  -- high resistivity phase

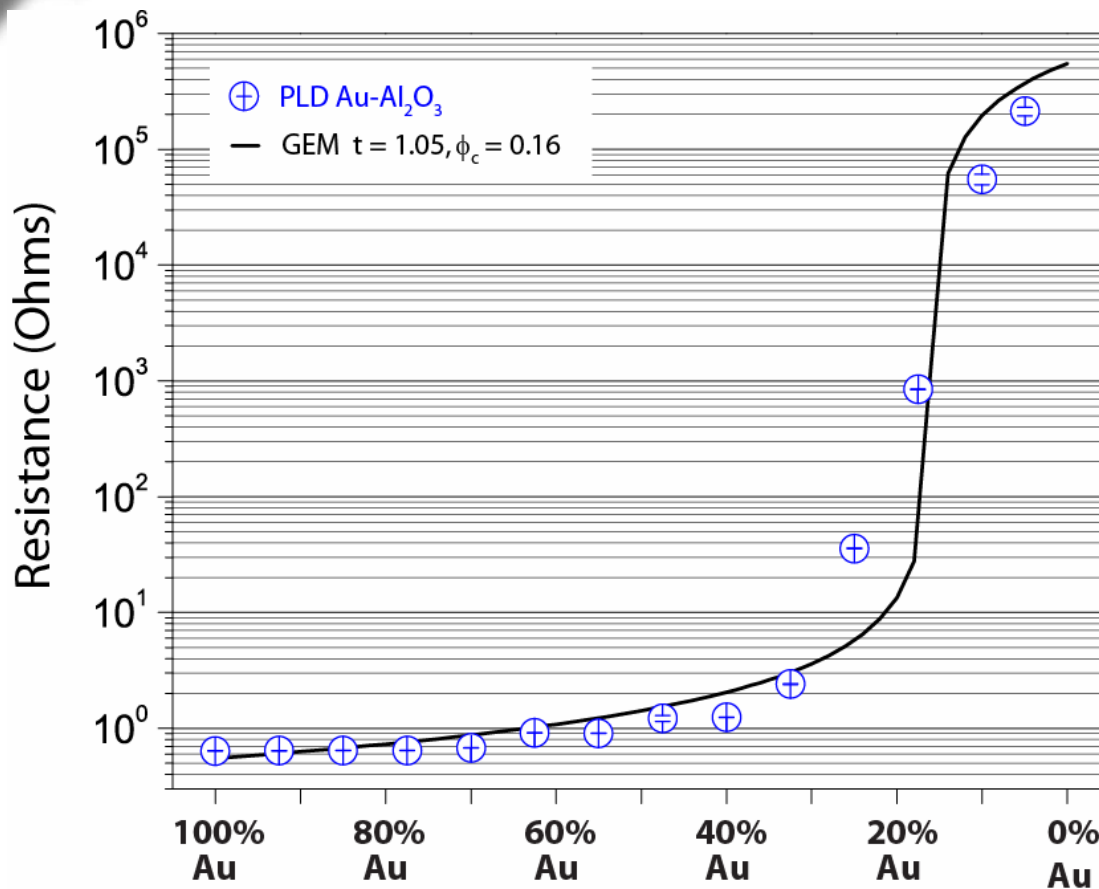
$\phi$  -- volume fraction

free parameters

$t$  -- percolation exponent

$\phi_c$  -- critical volume fraction

# Percolation Threshold



Subsequent testing of composites created with increased compositional resolution showed a distinct threshold where contact resistance increases sharply with small increase in filler percentage

**General Effective Media**  
(McLachlan 1987)

$$\frac{(1-\phi)\left(\rho_m^{1/t} - \rho_h^{1/t}\right)}{\rho_m^{1/t} + \rho_h^{1/t} \left(\frac{1-\phi_c}{\phi_c}\right)} + \frac{\phi\left(\rho_m^{1/t} - \rho_l^{1/t}\right)}{\rho_m^{1/t} + \rho_l^{1/t} \left(\frac{1-\phi_c}{\phi_c}\right)} = 0$$

unknown parameters

$\rho_m$  -- composite resistivity

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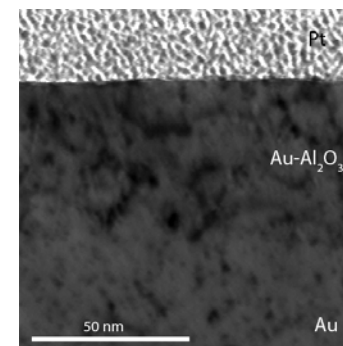
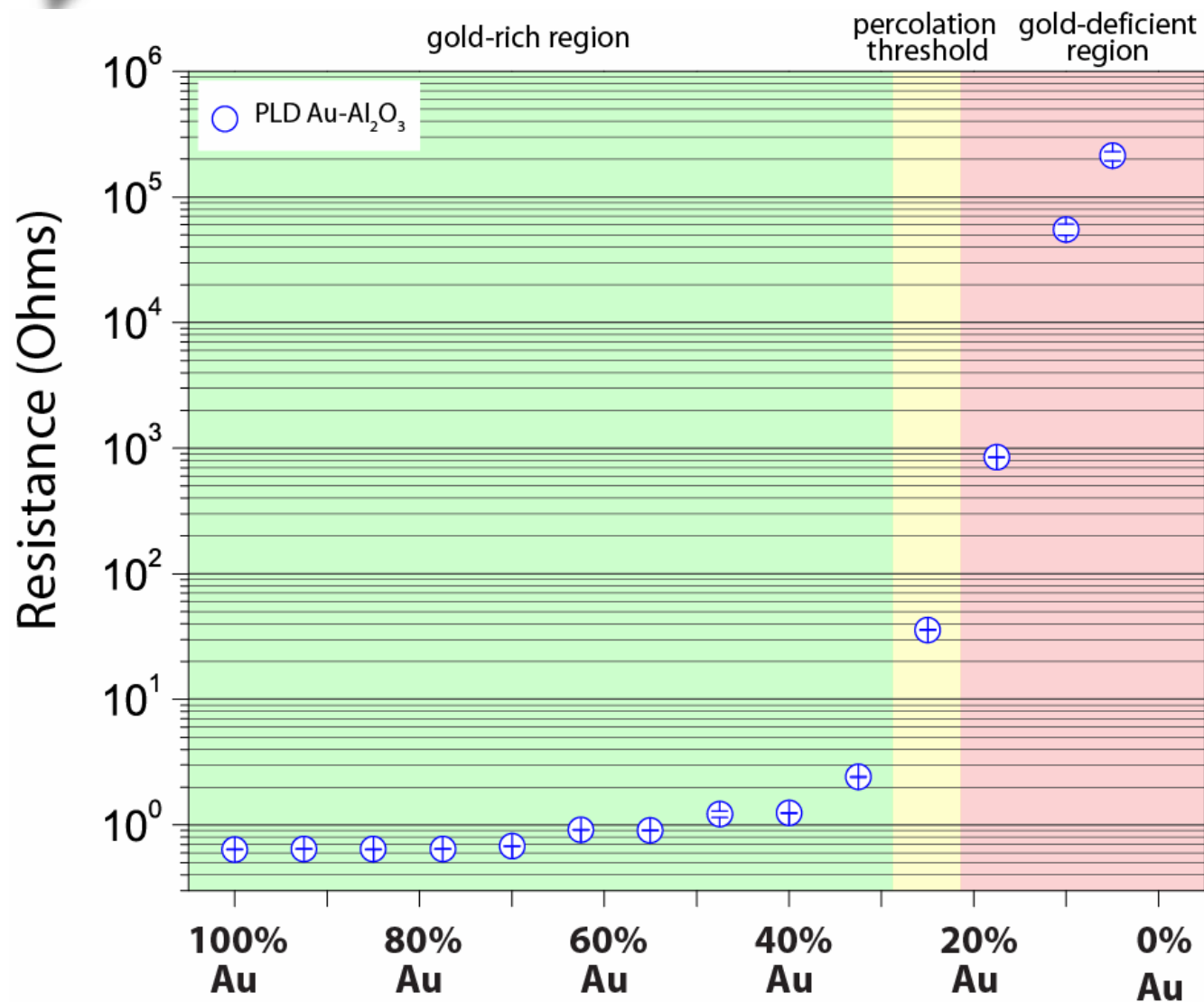
$\phi$  -- volume fraction

free parameters

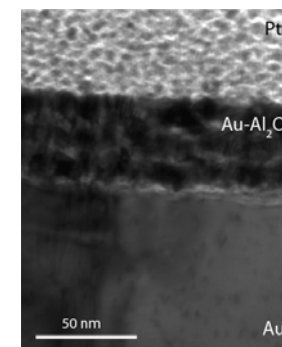
$t$  -- percolation exponent

$\phi_c$  -- critical volume fraction

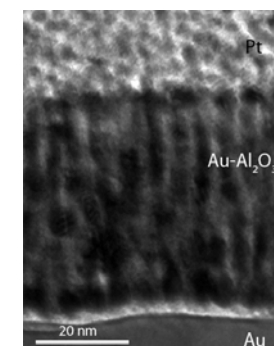
# Percolation Threshold



90% Au



50% Au



20% Au



# Conclusions

- **Co-deposited thin film electrical contact composites can be created which simultaneously exhibit good conductivity and reduced adhesion compared to a self-mated purely metallic contact**
- **The nano-scale structural morphology of the composite film strongly determines the effectiveness of the composite at conducting electrical current (percolation limit)**
- **Significant freedom exists in the deposition methods (co-sputtering, evaporation, etc.) used to create the composite films, as well as the materials available for use**
- **Significant refinement and optimization of the deposited film structure could lead to highly conductive, non-adherent electrical contact materials for high-reliability MEMS devices ( ! )**

# Acknowledgements and Questions



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National  
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Michael T. Dugger  
James A. Knapp  
David M. Follstaedt

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